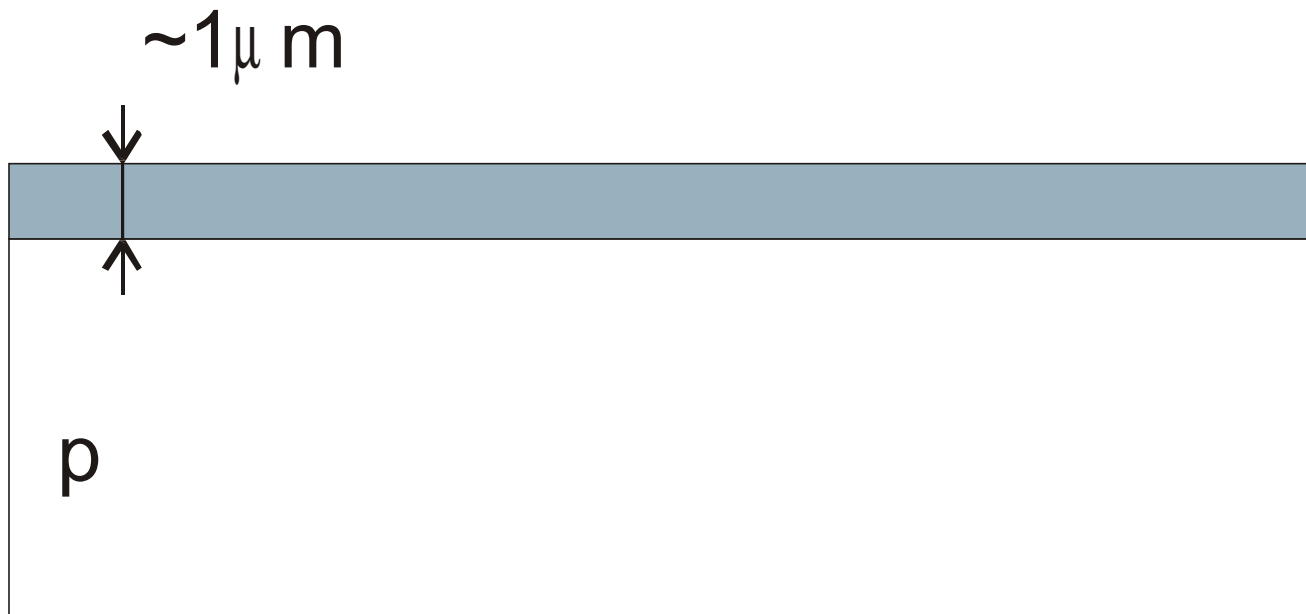
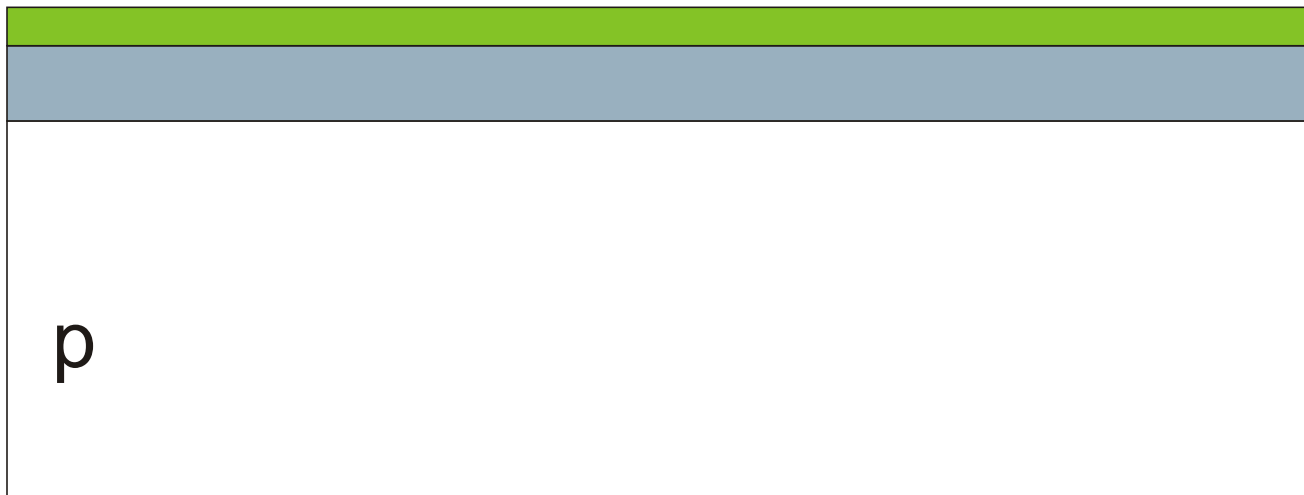


Manufacturing of NMOS Transistor

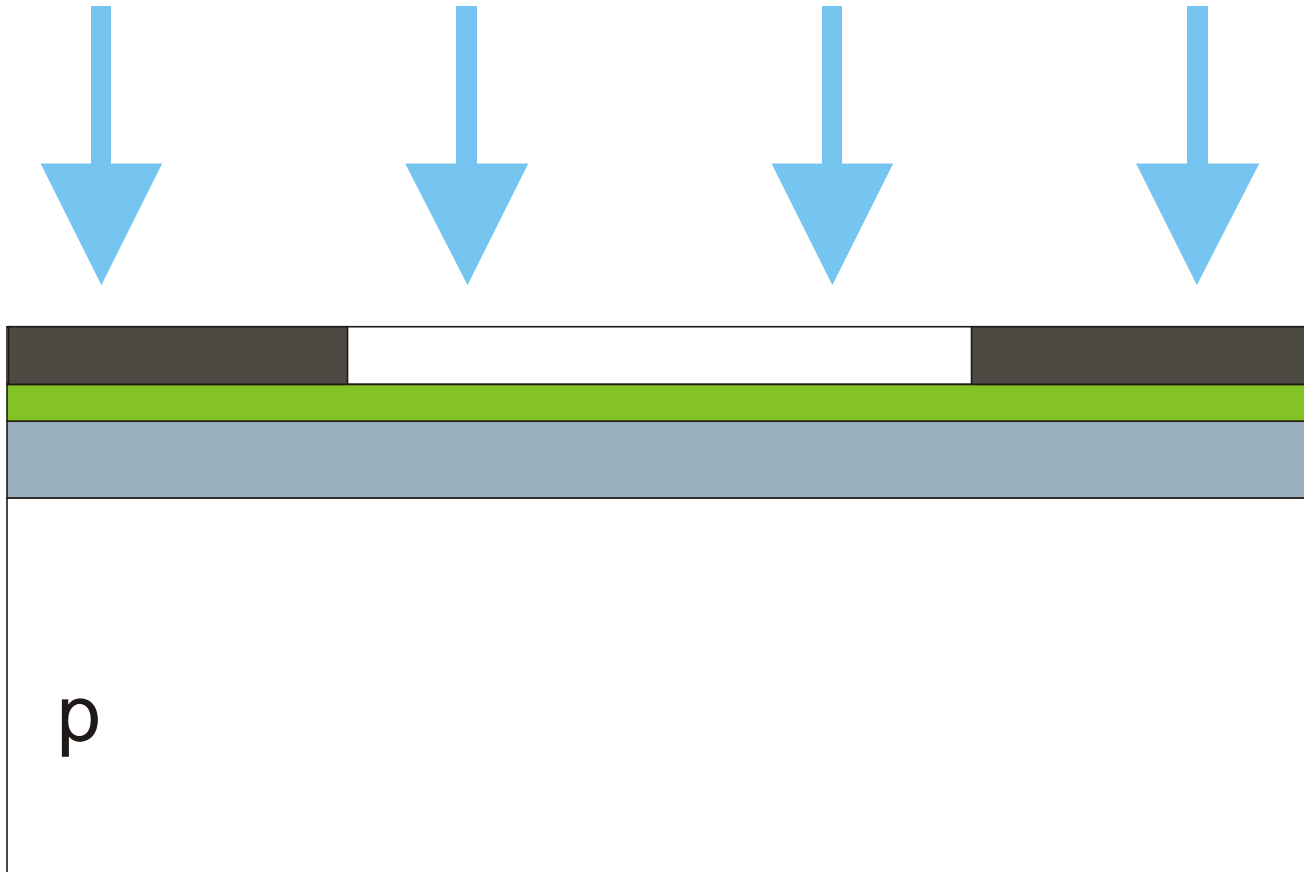
Substrate Oxidation



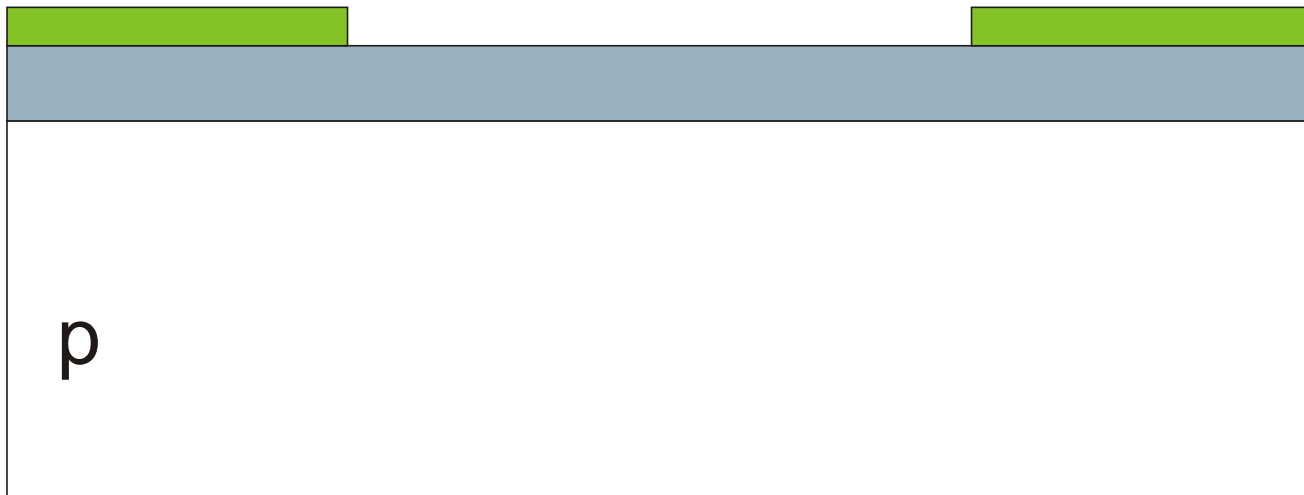
Deposition of Photoresist



Mask 1



Developing of Photoresist



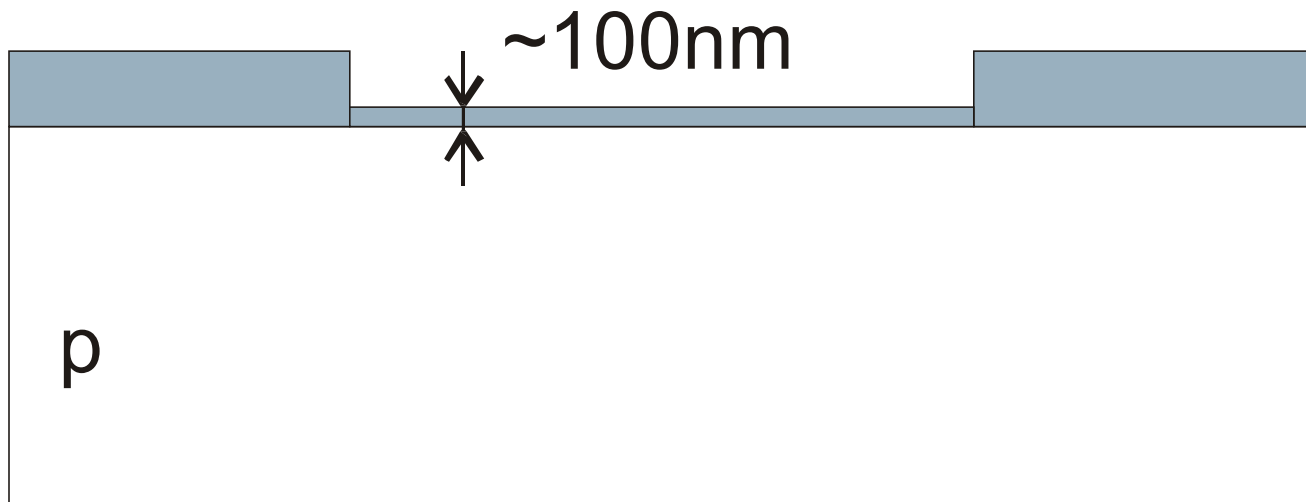
Oxide Etch



Removal of Photoresist



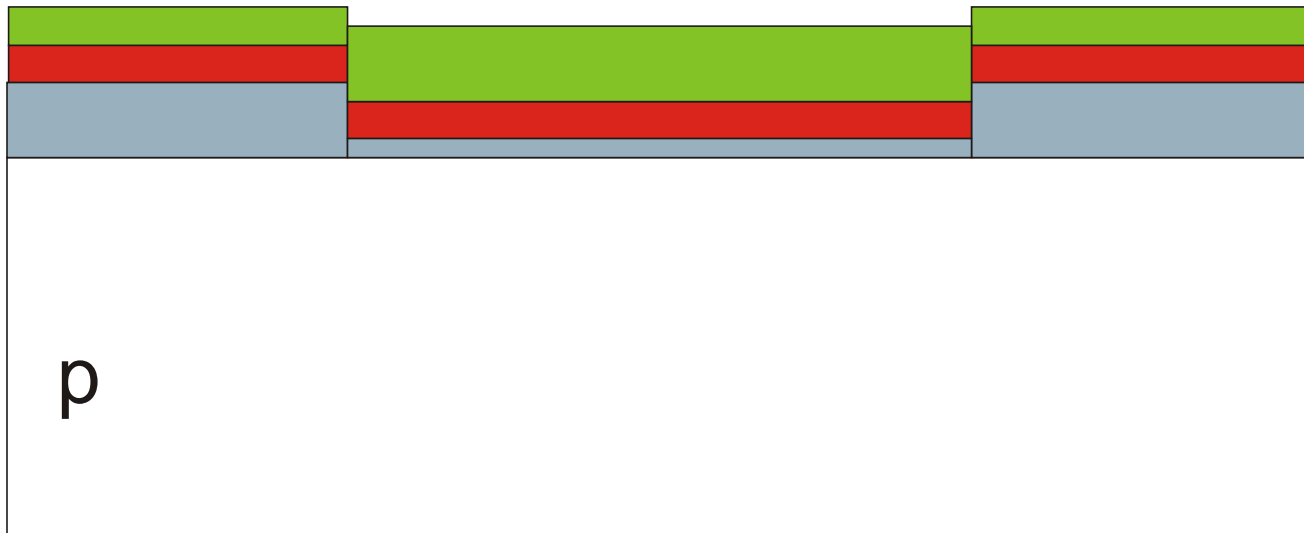
Deposition of Thin Oxide



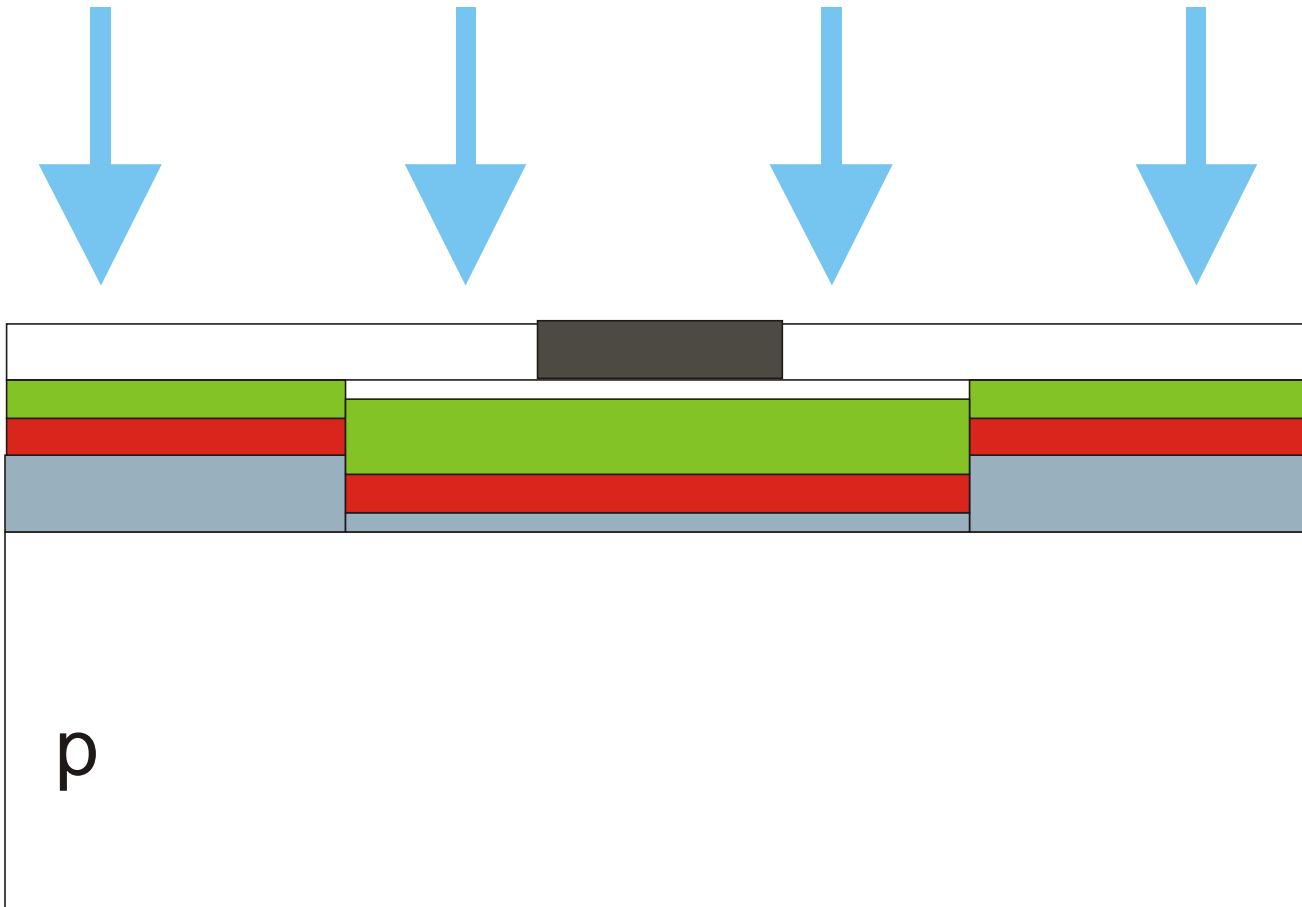
Deposition of Polysilicon



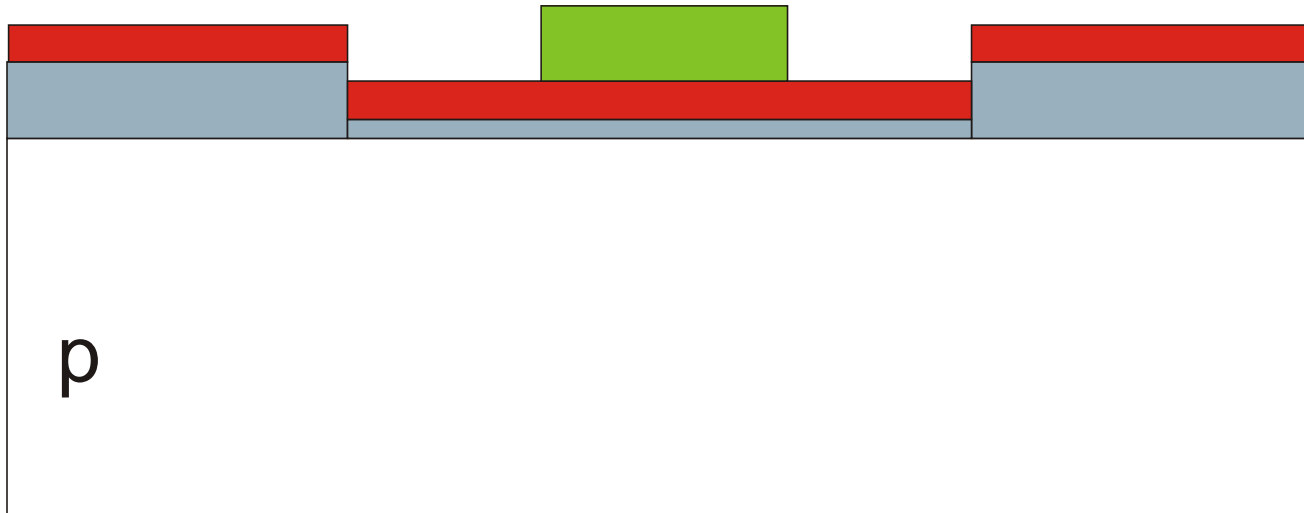
Deposition of Photoresist



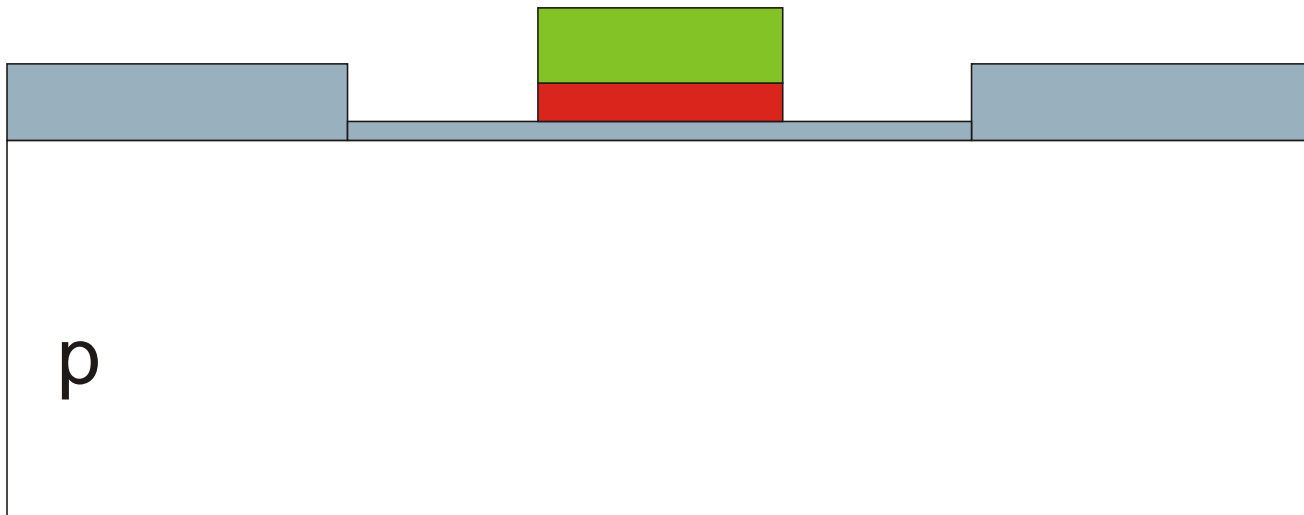
Mask 2



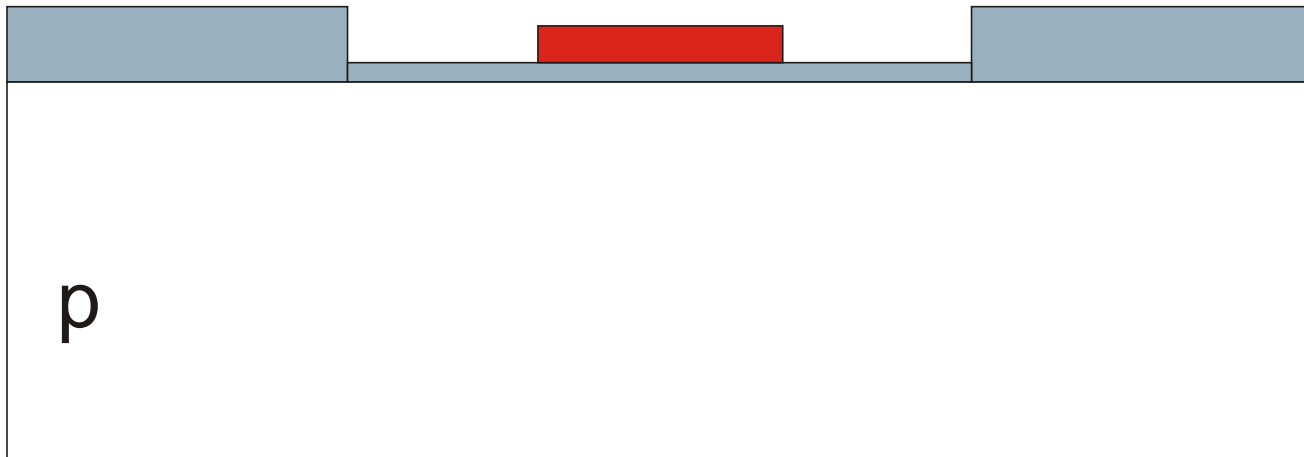
Developing of Photoresist



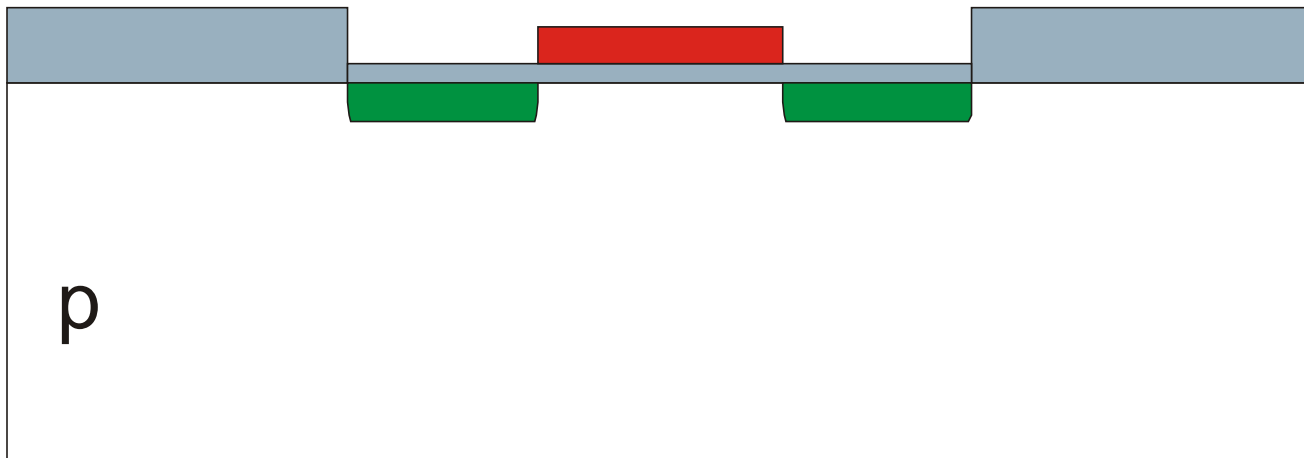
Polysilicon Etch



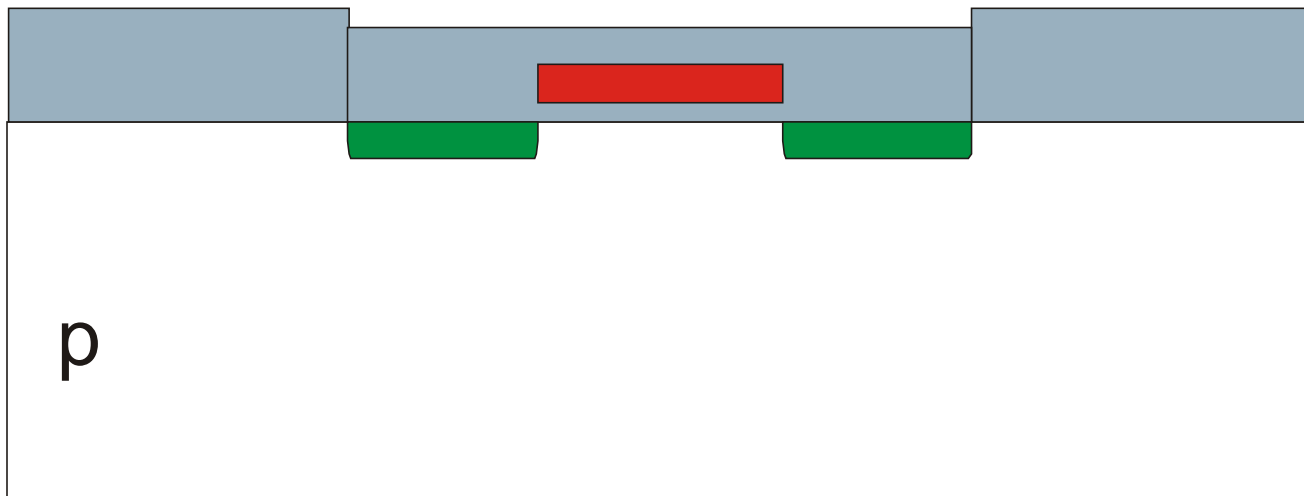
Removal of Photoresist



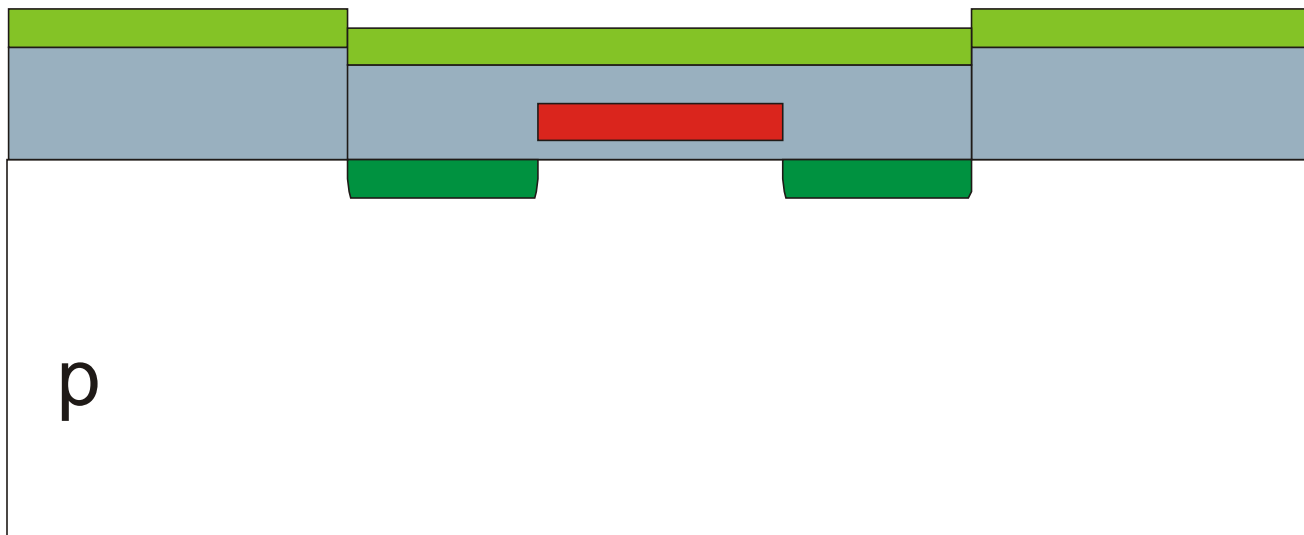
Drain and Source Implantation



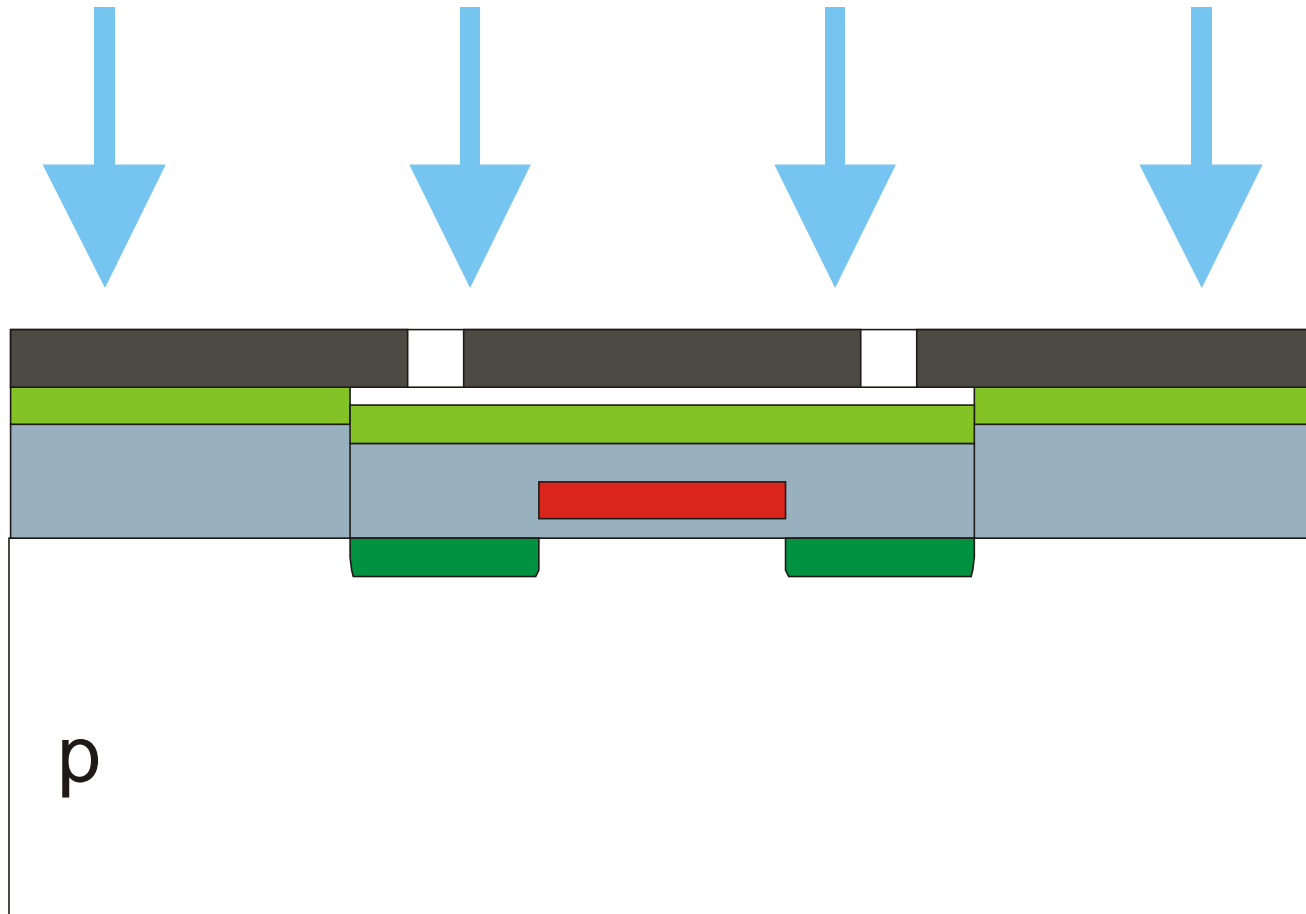
Deposition of Insulating Layer



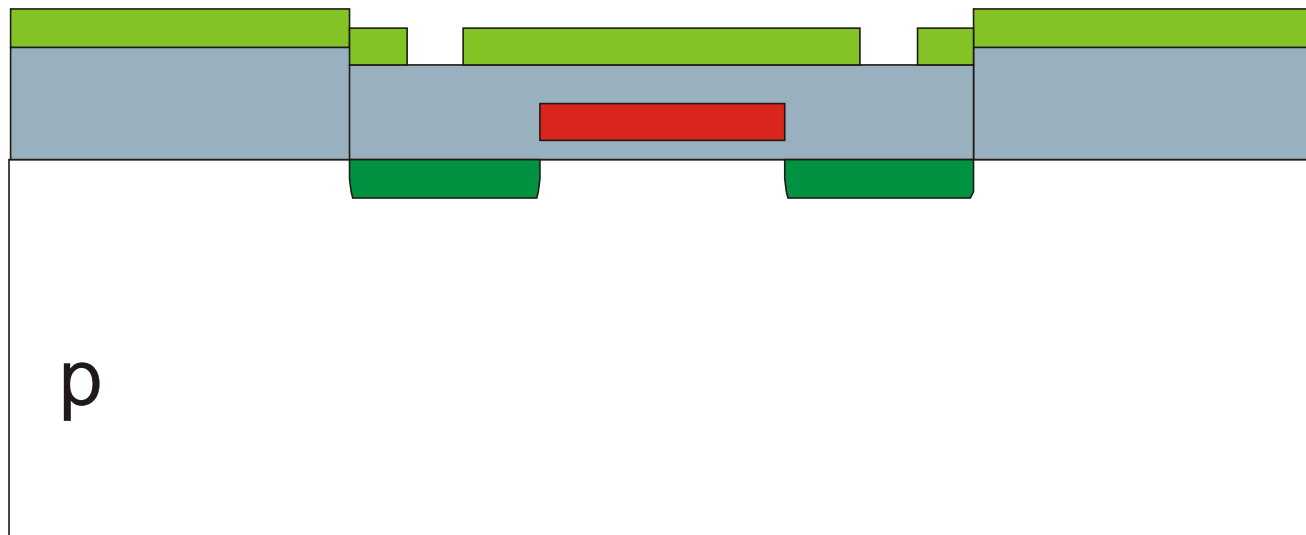
Deposition of Photoresist



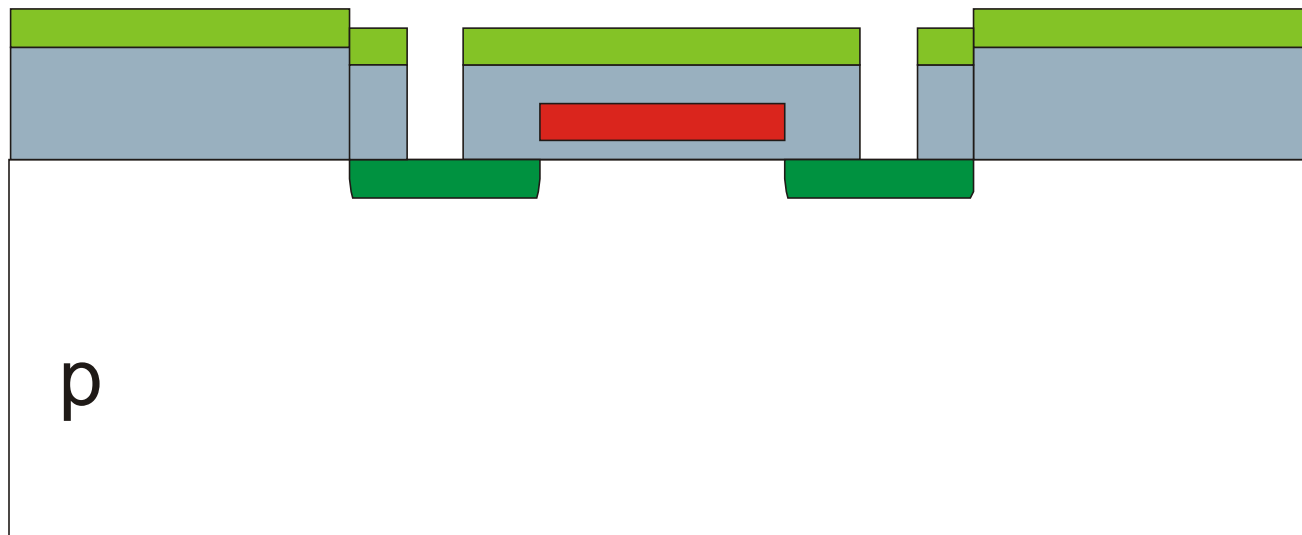
Mask 3



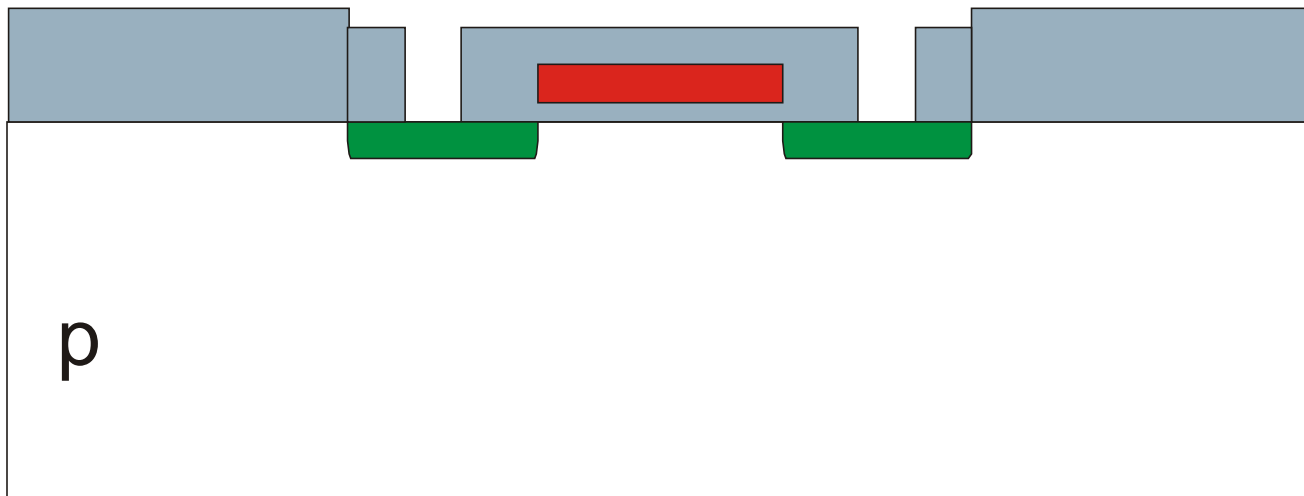
Developing of Photoresist



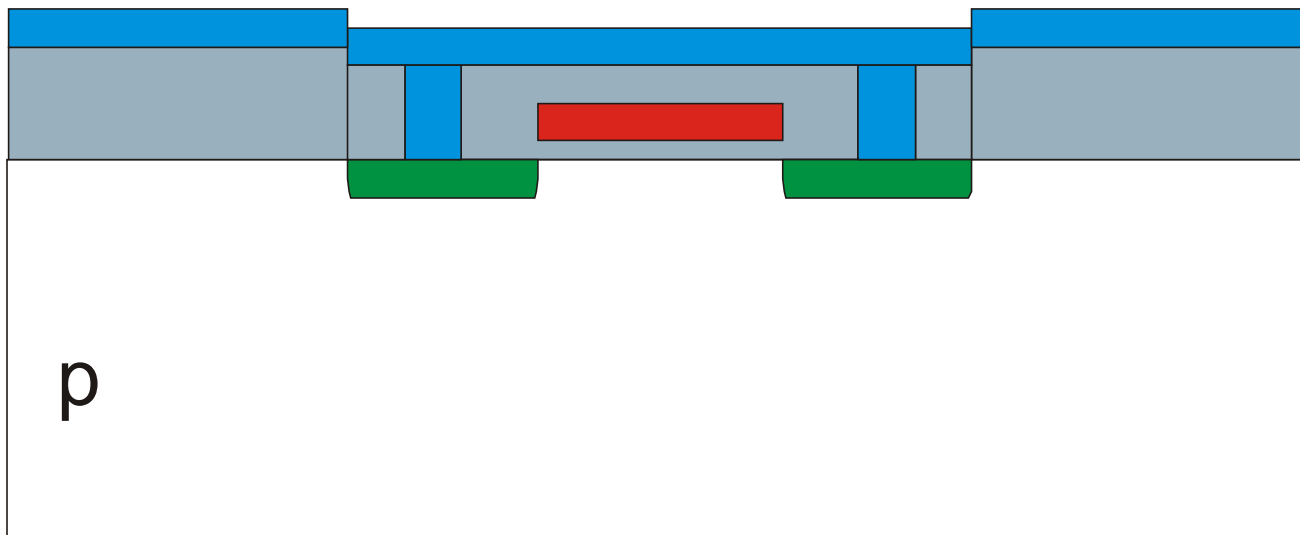
Oxide Etch



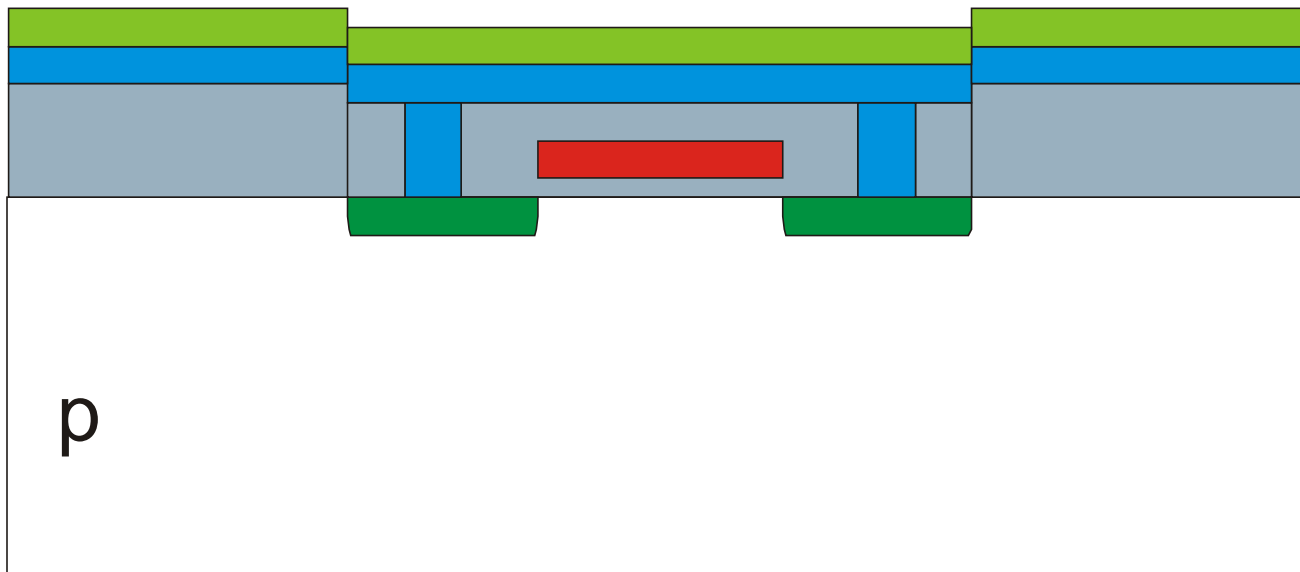
Removal of Photoresist



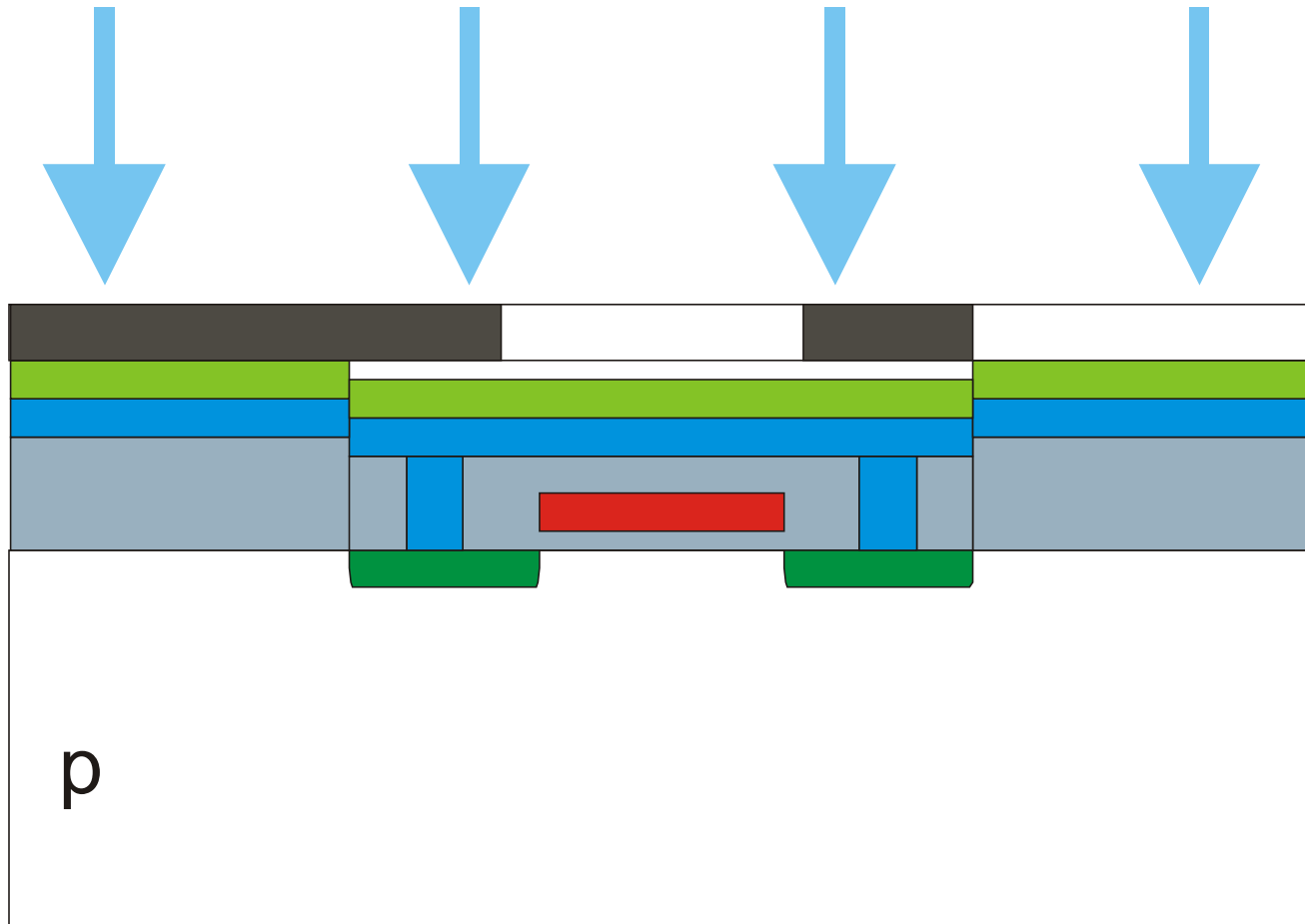
Metal Deposition



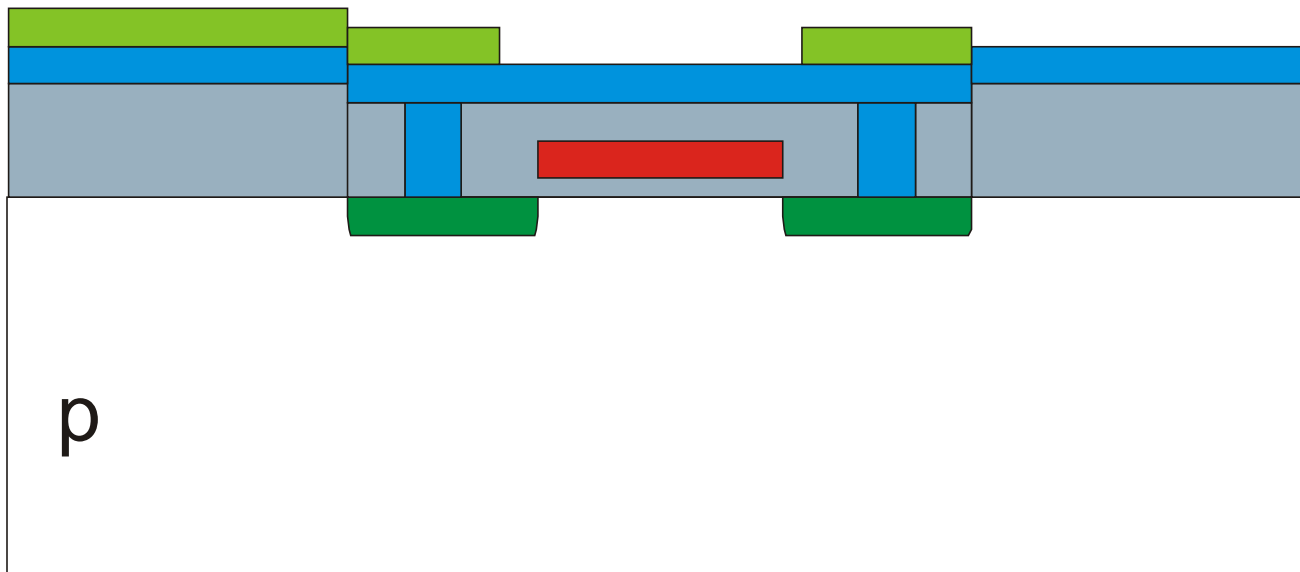
Photoresist Deposition



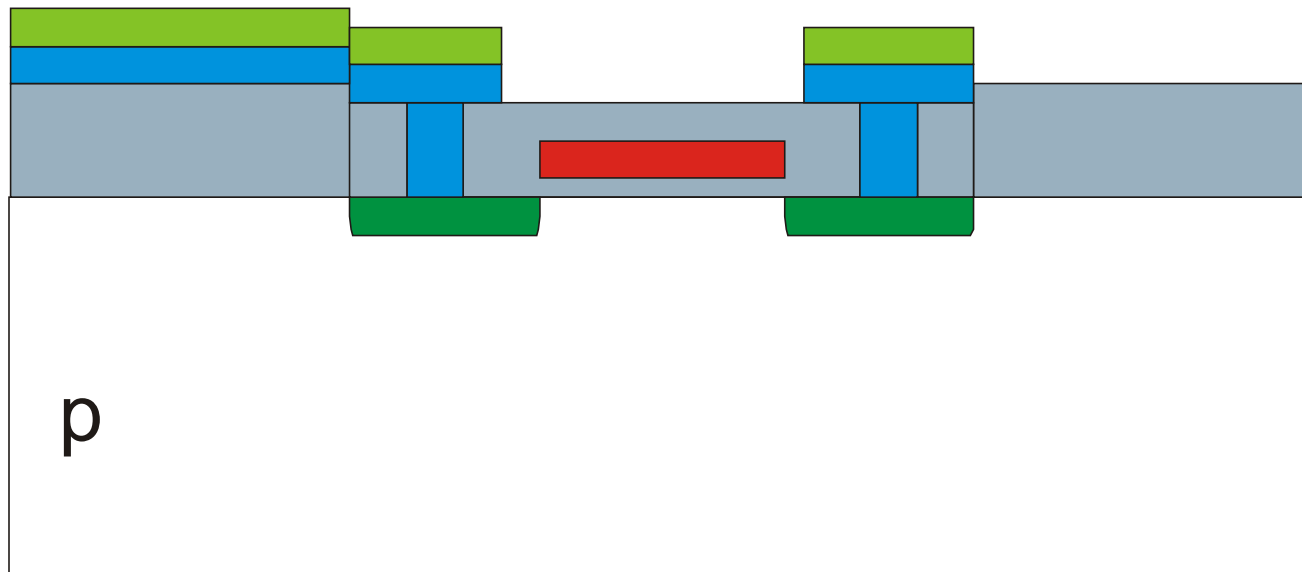
Mask 4



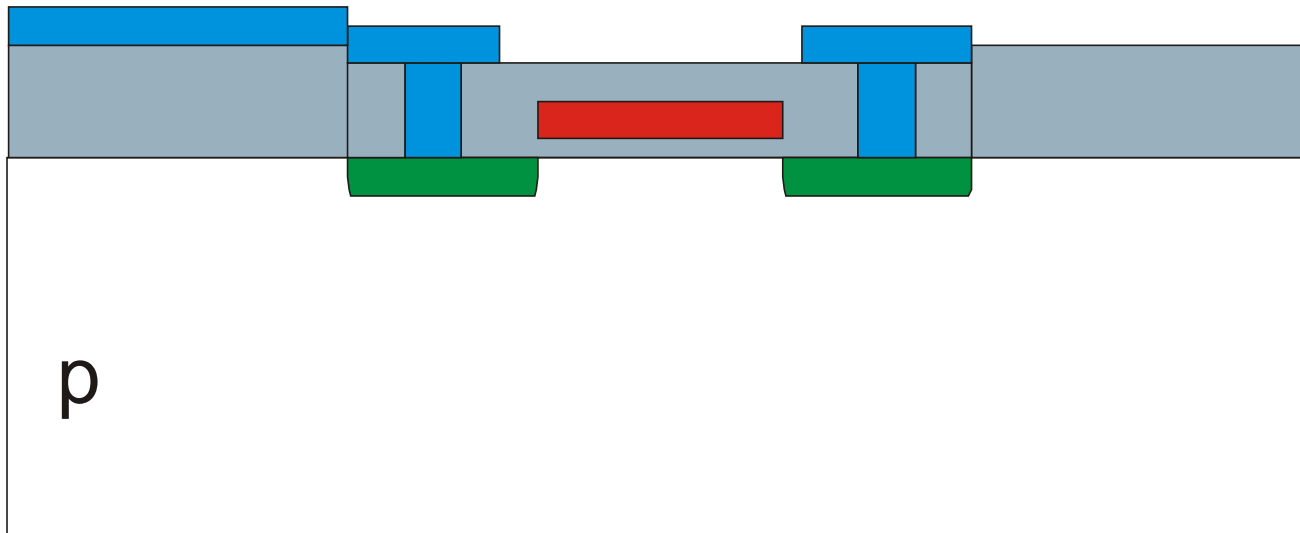
Developing of Photoresist



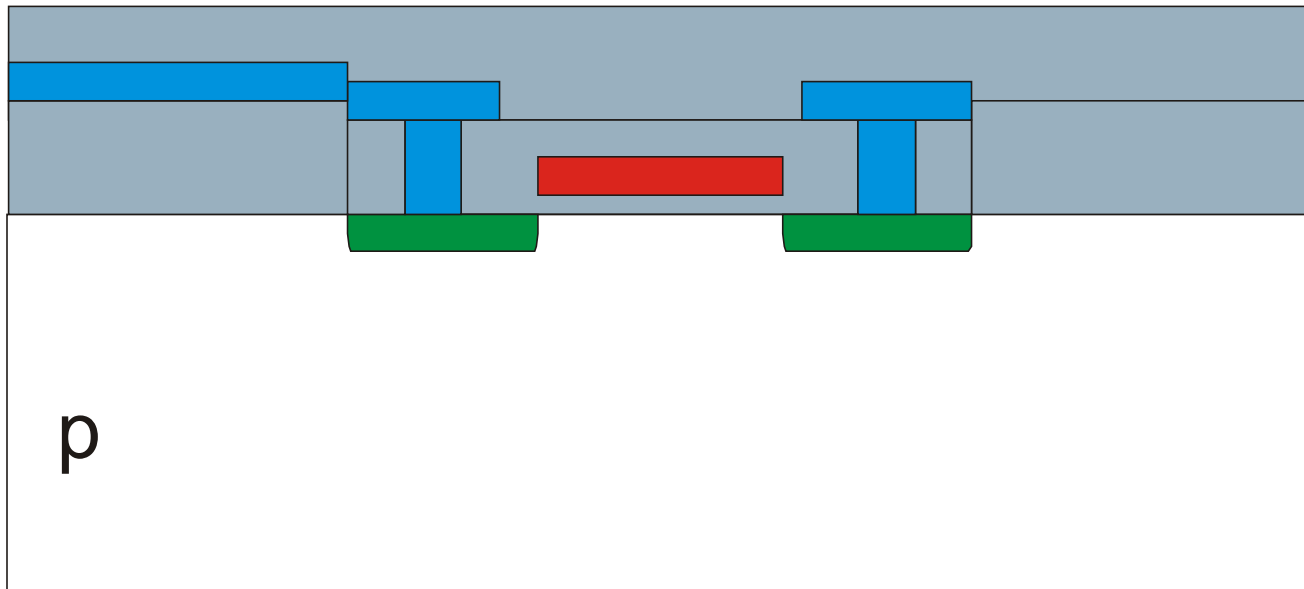
Metallization Etch



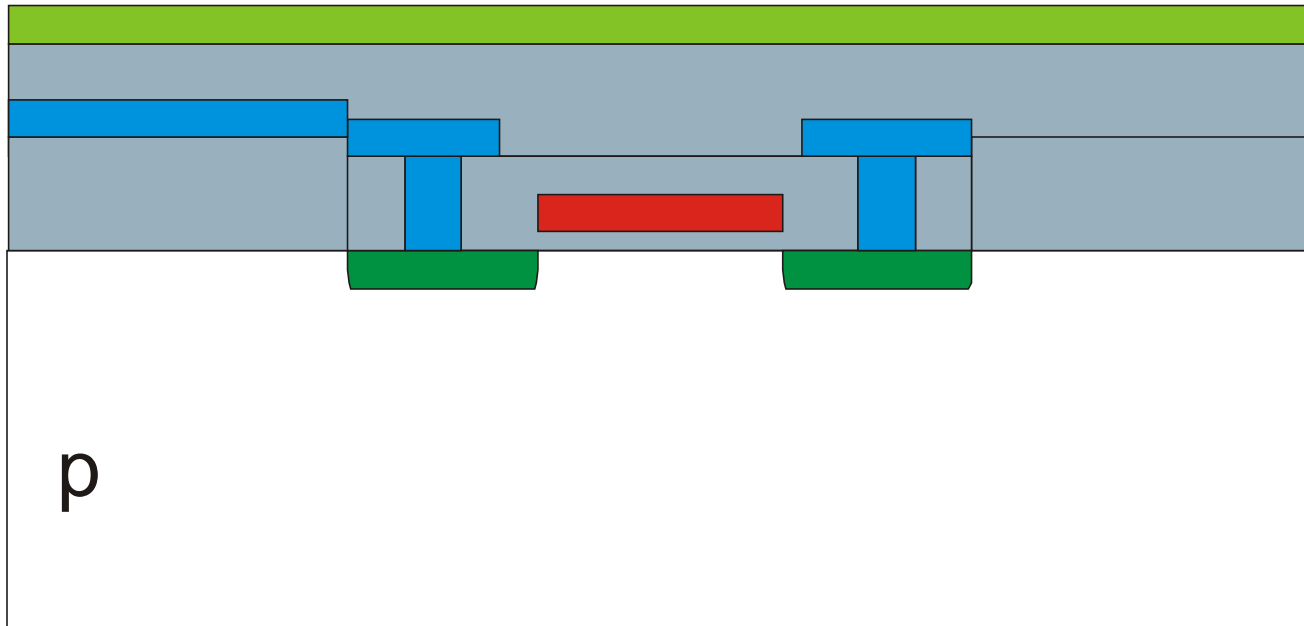
Removal of Photoresist



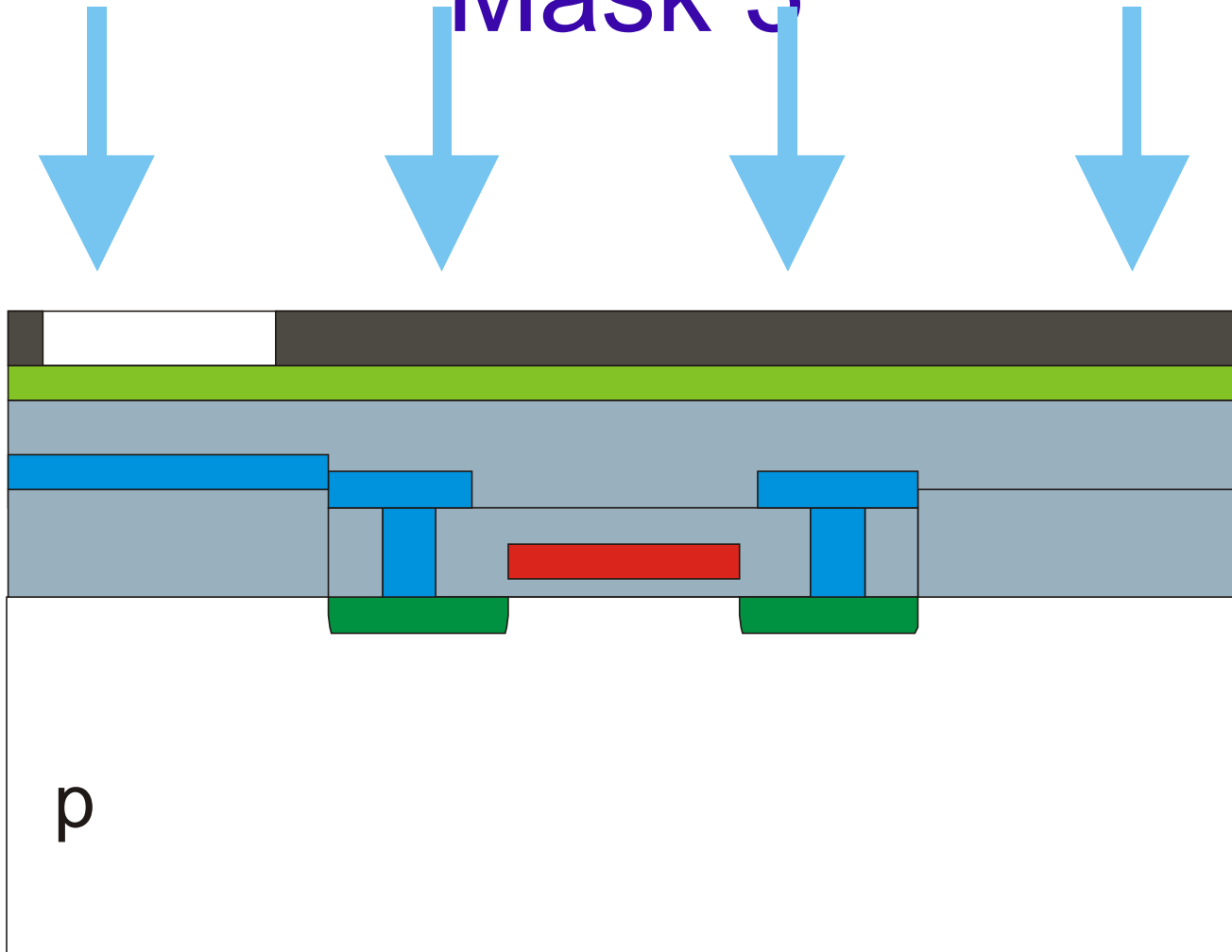
Deposition of Passivation Layer



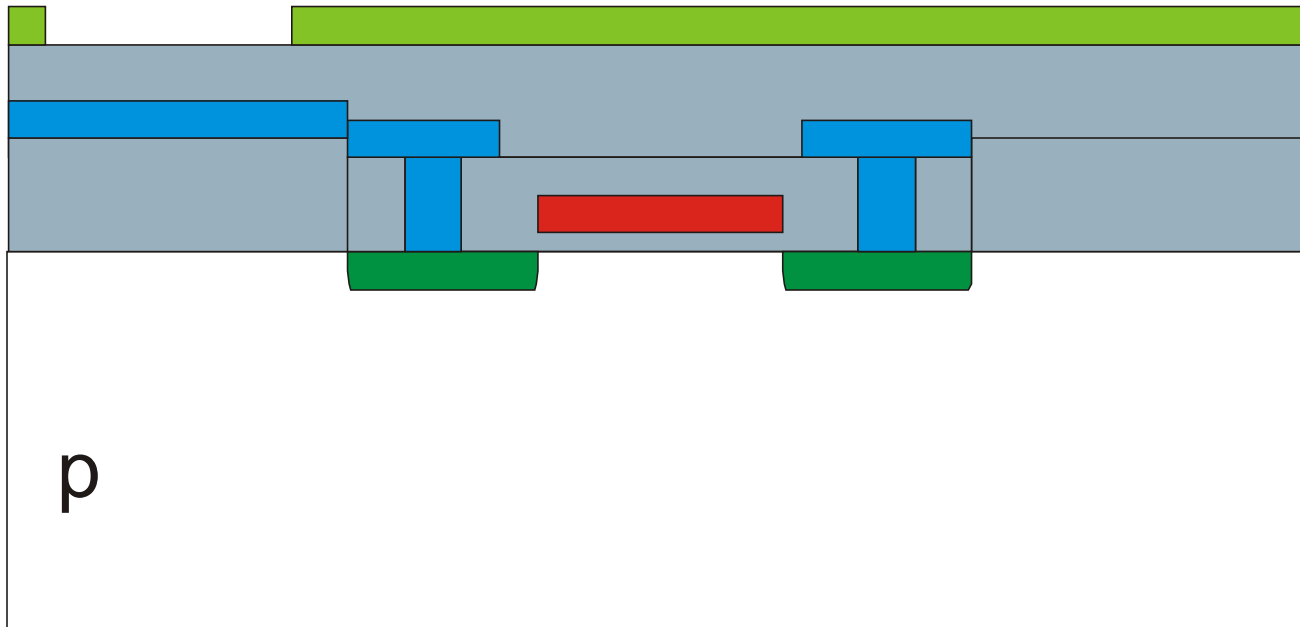
Deposition of Photoresist



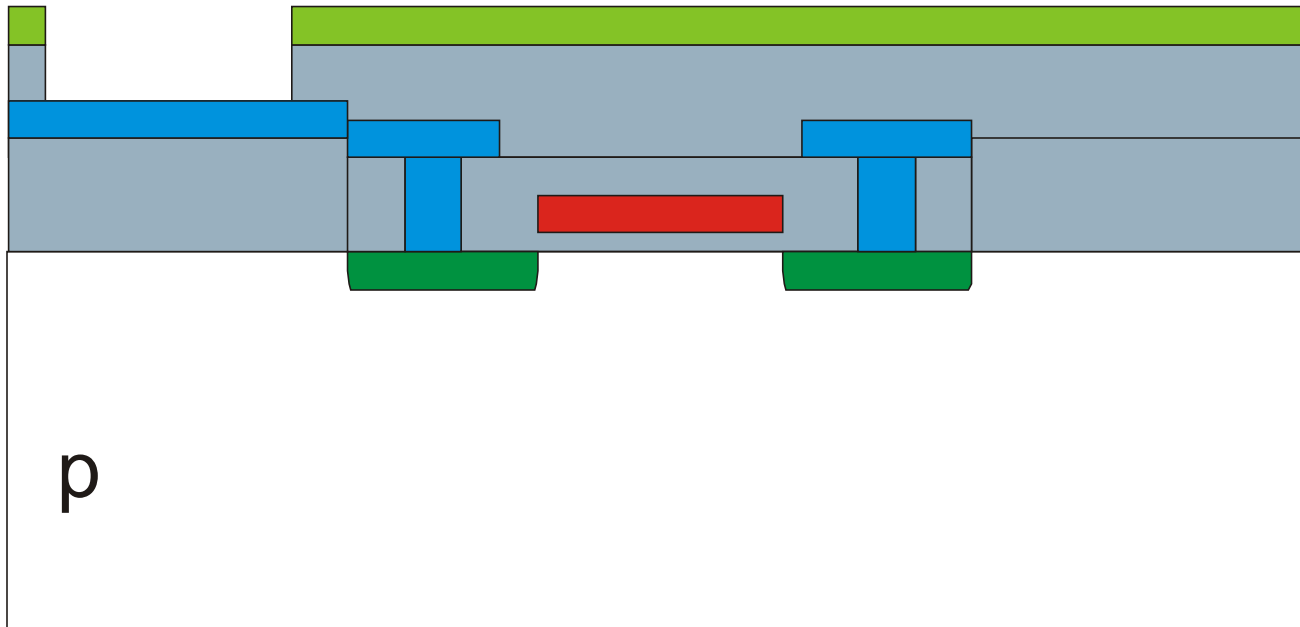
Mask 5



Developing of Photoresist



Oxide Etch



Removal of Photoresist

